SENTECH Erfolg durch Leistung

Berlin, 9/17/2019

<u>Aktuelles Experiment:</u>
noname.rcp

<u>Modellbeschreibung</u>

Number	Layer Name	Thickness [nm]	Refr. Index [632.8 nm]	Fitted
0	Air	-	1.000	no
1	NoName0	93.77	3.010	yes
2	Silicon DUV-NIR	-	3.874	no

<u>Fit parameter</u>

Fit parameter	Fit result
[1,1] NoName0: Thickness [nm]	93.77

<u>All parameter</u>

Parameter	Value
[1] Wavelength [nm]	632.8
[1] Angle [°]	70.00
[1] Time [s]	0.0
[1] Temperature [°C]	23.5
[1] Sample rotation [°]	0.00
[1] Depol. D0	1.0000
[1] Depol. D1	0.0000
[1] Depol. D2	0.0000
[1] Beam diameter	4.00
[1] Aperture diameter	4.00
[1,1] Thickness variation	10.0
[1] Wavelength resolution (nm)	0.0
[1] Angle variation	3.0
[1] Angle offset [°]	0.00
[1] Wavelength Offset (nm)	0.00
[1] Wavelength Linear	1.00000
[1] Fraction Overlayer	1.000
[1] Backside Factor	1.000
Air: Refr. index	1.000
Air: Absorption	0.000
Air: N Offset	0.00000
Air: K Offset	0.00000

page 1 of 3

[1,1] NoName0: Thickness [nm]	93.77
NoName0: N0	3.000
NoName0: N1	40.0
NoName0: N2	0.0
NoName0: K0	0.000
NoName0: K1	0.000
NoName0: K2	0.000
NoName0: N Offset	0.00000
NoName0: K Offset	0.00000
Silicon DUV-NIR: N Offset	0.00000
Silicon DUV-NIR: K Offset	0.00000
Pola.Pos.	45.00
Pola.Offs.	0.00
Ret.Axis	0.00
Ret.Phase	90.00
Eta	1.00000
Ana.Offs.	0.00
Ana.Offs.Lin.	0.00
Ana.Offs.Quadr.	0.00
Psi Offs.	0.00
Psi Lin.	0.00
Psi Quadr.	0.00
Delta Offs.	0.00
Delta Lin.	0.00
Delta Quadr.	0.00
MSE	46.92716738

Measured Data

RRM001-042 / Psi, Delta / Spectral range: 300.2 nm - 1050.0 nm / Angle of incidence: 60.00 ° / 9/17/2019 2:35:26 PM

RRM001-042 / Ps …
—— ψ / φ= 60.0°

RRM001-042 / Ps …
—— Δ / φ= 60.0°